

ABSTRACT

COATING COMPOSITION AND LOW DIELECTRIC SILICEOUS MATERIAL PRODUCED BY USING SAME

5 The present invention provides a coating composition,
which can simply produce a porous siliceous film having
excellent mechanical strength and, at the same time,
possessing a stable very low level of dielectric and good
chemical resistance to various chemicals, and to provide a
10 process for producing a siliceous material using the same. The
coating composition according to the present invention
comprises a polyalkylsilazane compound, an acetoxysilane
compound, an organic solvent, and, if necessary, a pore forming
material. The present invention also provides a siliceous
material produced by firing the coating composition and a
process for producing the same.